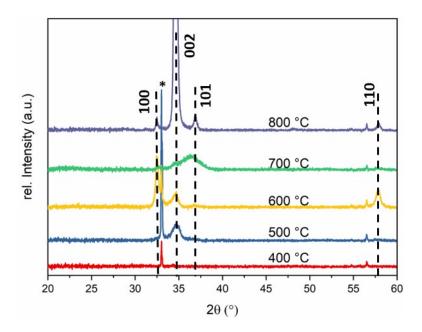
## **Supplementary Information**

## CVD grown $GaSb_xN_{1-x}$ films as visible-light active photoanodes.

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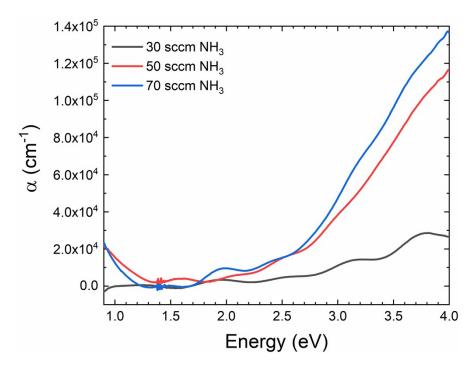
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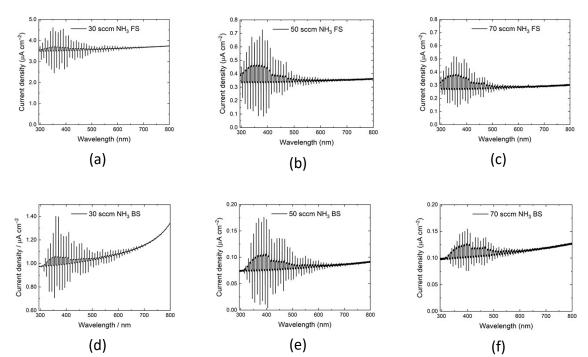
**Fig. S1:** X-ray diffraction patterns of GaN thin films deposited on Si(100) at different substrate temperatures using  $[Ga(Me)(dpamd)_2]$  and NH<sub>3</sub> as precursors. (Reference: JCPDS No. 00-002-1078). The asterisk denotes the forbidden (002) reflex of the underlying Si.

**Table S1:** Composition (as determined via RBS/NRA) of GaN thin films grown on Si(100) as a function of deposition temperature .

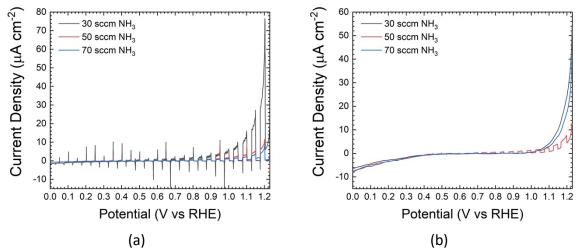
T <sub>dep</sub> (°C)	C (at.%)	N (at.%)	O (at.%)	Ga/N
400	8.6	10.7	48.6	3
500	5.2	41.0	6.1	1.2
600	7.3	40.6	3.5	1.2
700	7.9	41.5	2.6	1.2
800	2.5	43.2	3.8	1.2



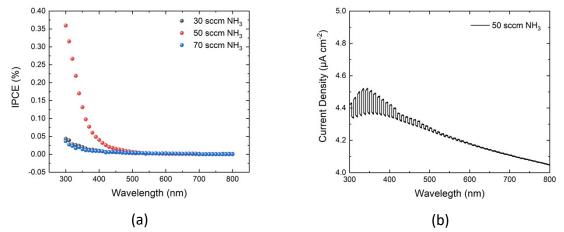
**Fig. S2:** Absorption coefficient for the  $GaSb_xN_{1-x}$  thin films on FTO substrates deposited at 600 °C.



**Fig. S3:** Wavelength dependent photocurrent transients for  $GaSb_xN_{1-x}$  thin films measured at 1.25 V vs. RHE in borate buffer (0.1 M, pH 9.2) containing 0.1 M Na<sub>2</sub>SO<sub>3</sub> under intermittent monochromatic irradiation (5 s light, 5 s dark) for the thin films on FTO (prepared at 600 °C) from the (a)-(c) front side (FS) and (d)-(f) back side (BS).



**Fig. S4:** Potential-dependent photocurrent for  $GaSb_xN_{1-x}$  thin films measured at thin electrodes in borate buffer (0.1 M, pH 9.2) in the presence of 0.1 M Na<sub>2</sub>SO<sub>3</sub> under intermittent (5 s light / 5 s dark) solar irradiation (Xe-Lamp with a AM-1.5G filter, 100 mW/cm<sup>2</sup>) (a) thin films on FTO, prepared at 600 °C and illuminated from the back (substrate) side, (b) thin films on GC (glassy carbon), prepared at 800 °C and illuminated from the front (electrolyte) side.



**Fig. S5:** (a) Photoaction spectra of the  $GaSb_xN_{1-x}$  thin films deposited on glassy carbon substrates (prepared at 800 °C) measured at 1.25 V vs. RHE in borate buffer (0.1 M, pH 9.2) with addition of  $Na_2SO_3$  (0.1 M) under intermittent monochromatic irradiation from the frontside (FS) (600 s idle at beginning, next 5 s light / 5 s dark), (b) corresponding photocurrent transients measured at the same conditions with interval of 10 nm.